

JAN 03 2006

PATENT

Atty. Dkt. No. APPM/007761/IMPLANT/CONDUCTIVE/JB1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:
Ito, et al

Serial No.: 10/630,293

Confirmation No.: 9715

Filed: July 30, 2003

For: Ion Implantation Method, SOI
Wafer Manufacturing Method
and Ion Implantation System

Group Art Unit: 2823

Examiner: George R. Fourson, III

MAIL STOP AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450CERTIFICATE OF FACSIMILE TRANSMISSION UNDER
37 CFR 1.8I hereby certify that this correspondence and the documents
referred to as attached therein are being facsimile transmitted
to the U.S. Patent and Trademark Office to the fax number
indicated by the Examiner, namely, fax number (571) 273-
8300 to the attention of the named Examiner, on the date
below.January 3, 2006
Date

Signature

Dear Sir:

RESPONSE TO FINAL OFFICE ACTION DATED NOVEMBER 1, 2005

In response to the Final Office Action dated November 1, 2005, having a shortened statutory period for response set to expire on February 1, 2006, please enter this response and reconsider the claims pending in the application for reasons discussed below. Although Applicants believe that no additional fees are due in connection with this response, the Commissioner is hereby authorized to charge counsel's Deposit Account No. 20-0782/APPM/007761/KMT, for any fees, including extension of time fees or excess claim fees, required to make this response timely and acceptable to the Office.

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper. **Remarks** begin on page 5 of this paper.

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